UI Science Profile Equipment for next generation

UI SCIENCE Co., ltd.

Profile of UI SCIENCE

OHead office UI SCIENCE Co., ltd.

OAddress 1059-5 TAKATA KASHIWA City CHIBA JAPAN

TEL 04-7137-7383 FAX 04-7137-7384

OCompany Profile

Established September 2016
Capital 100,000,000Jpy

Maine bank Chiba bank, Keiyo bank

Representative

Director and President Shinichi Umemoto

Sales results 2022 1,000,000,000Jpy

Sales record 14 equipment

OSales equipment type

RtoR Connecter Plating Equipment

Full Auto Wafer Plating System

Semi Auto Wafer Plating System

Lead frame Plating Equipment Cut Sheet or RtoR

PCB Plating Equipment,

Plating Tool (Silicon mask etc)



Introduction of UI SCIENCE

Concept of Equipment

- •We are familiar with the latest plating equipment technology. State-of-the-art equipment group.
- •Our equipment was designed for high spec ideas.

 This is a custom-made Equipment for which you can request specifications.

Organizational Structure

Officer Sales
Accounting, general affairs
Technical design
Production control
Production
System Control

Confidential

Introduction of Plating equipment.

Full Auto Wafer Plating System

Model : FAWPS-04~08

Chamber : 4~8 Chamber

Through put : MAX 10000wafer/month

Wafer size : $\phi 75 - \phi 100 - \phi 125 - \phi 150 - \phi 200$

3inch-4inch-5inch-6inch-8inch

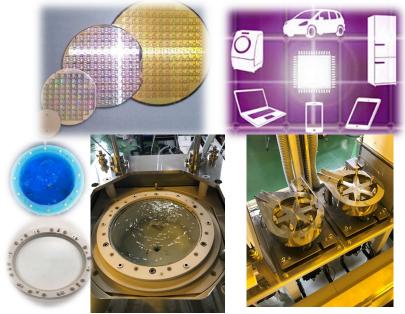
Plating spec : Cu, NI, Au, Sn etc

Wafer material :Silicon Wafer /GaAs Wafer

GaN Wafer etc

OConcept of system

- Equipped with SCARA robot for stable transportation and high quality plating.
- The two-handed SCARA robot does not stain the wafer.
- Production recipe, production record, production recording function installed (compliant with SECS standard)
- · High quality plating supported by original face down Chamber
- Supports high-quality plating by installing wafer contact ring cleaning function





(Model 2018 ϕ 200-8chamber-4SRD)

Introduction of Plating equipment.

Semi Auto Wafer Plating System

Model: SAWPS-04~14

Chamber : 4~14 Chamber

Through put : MAX 10000wafer/month

Wafer size : $\phi 75 - \phi 100 - \phi 125 - \phi 150 - \phi 200$

3inch-4inch-5inch-6inch-8inch

Plating spec : Cu, NI, Au, Sn etc

Wafer material :Silicon Wafer /GaAs Wafer

GaN Wafer etc



Ф200 8inch Cu 4+4+2



Φ200 8inch Cu 8+6





Introduction of Plating equipment.

RtoR Connecter Plating Equipment

Model : UIRC-01 ~04

Number of line : 1line~4line(MAX4line)

Drive speed : 1.0~25.0m/min

Production item: Connecter, Foop

: Thickness t0.06~t1.0mm

: Hight 5∼120mm

Basic plating spec :Ni+Pd+Au+Sn

: Cu+Sn+Reflow etc

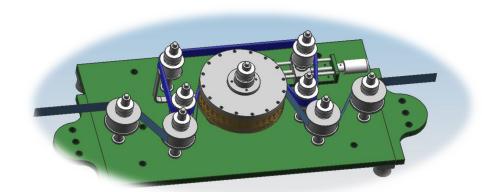
Material : Cu , SUS etc

OConcept of Equipment

narrow-pitch micro connector products and high quality plating support

Automotive connector products and high quality plating support

 High-precision partial plating is possible by processing various parts plating tool





Introduction of Plating equipment.

Lead frame Plating Equipment

RtoR type plating equipment

Model : UIRLF-02 ~ 04

Number of line : 1line~4line(MAX4line)

Drive speed : $1.0 \sim 5.0 \text{m/min}$

Production item: Lead frame, Foop

: Thickness t0.06~t1.0mm

: Hight 5~120mm

Basic plating spec :Ni+Pd+Au

: Cu + Ag etc

Material : Cu , SUS etc

OConcept of Equipment

- High-precision partial plating is possible by processing various parts plating tool
- •Spot plating position accuracy ± 0.07 mm achieved







Confidential

Introduction of Plating equipment.

Lead frame Plating Equipment

Cut sheet type plating equipment

Model : UICLF-02 ~ 04

Number of line : 1line~4line(MAX4line)

Conveyer speed: 1.0~2.0m/min

Production item: Lead frame cut sheet

: Thickness t0.06~t0.8mm

: Wide 50~100mm

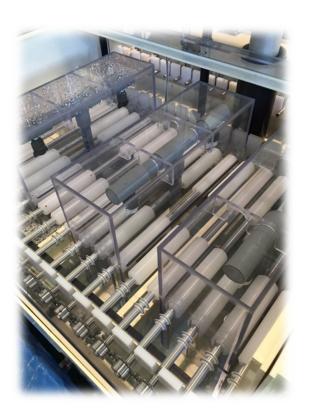
Basic plating spec :Ni+Pd+Au

: Cu + Ag etc

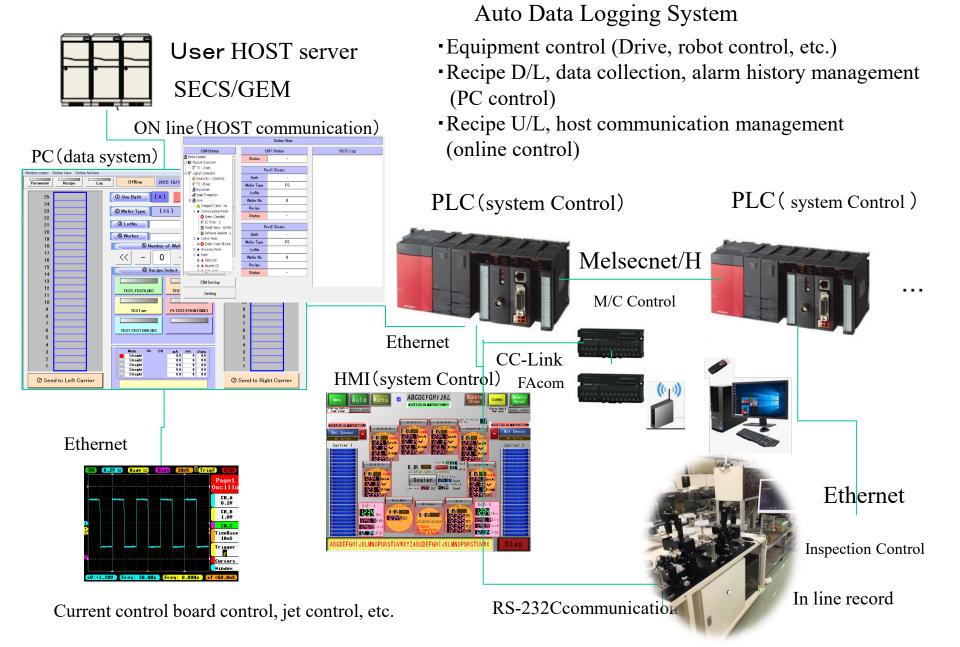
Material : Cu , SUS etc

OConcept of Equipment

- High-precision partial plating is possible by processing various parts plating tool
- Spot plating position accuracy ± 0.05 mm achieved



Introduction of control system (ADLS)



Access to UI SCIENCE

Always access to the station

35 minutes by train from Tokyo Station

60 minutes by train from Haneda Airport

75 minutes by bus

60 minutes by train from Narita Airport

90 minutes by bus



